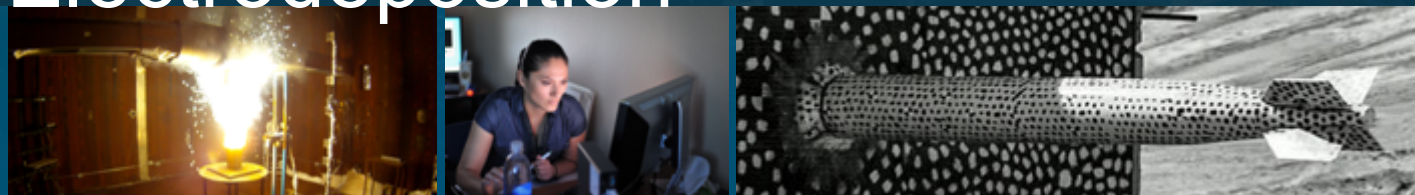




High Resolution, High Conductivity Components by Aerosol Jet Printing and Electrodeposition



Presented By

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THE 32ND ANNUAL INTERNATIONAL VIRTUAL
**SOLID FREEFORM
FABRICATION SYMPOSIUM**
— AN ADDITIVE MANUFACTURING CONFERENCE — 2021

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I. Introduction

- Additive manufacturing of electronics by aerosol jet printing.
- Options for enhancement of conductivity for printed parts.

II. Results:

- Printing of planar spiral inductors for transformer applications
- Deposition of Cu by electroless deposition.
- Deposition of Cu by electrodeposition.
- Impedance analysis of printed / inductors.

III. Conclusions and Future Work

Motivation: Additive Manufacturing of Electronic Parts



- **Traditional Electronics Manufacturing:**

- Mass Production.
- Low cost per unit, but high up-front cost.
- High cost for design modification and geometric complexity.

- **Additive Manufacturing / 3D printing**

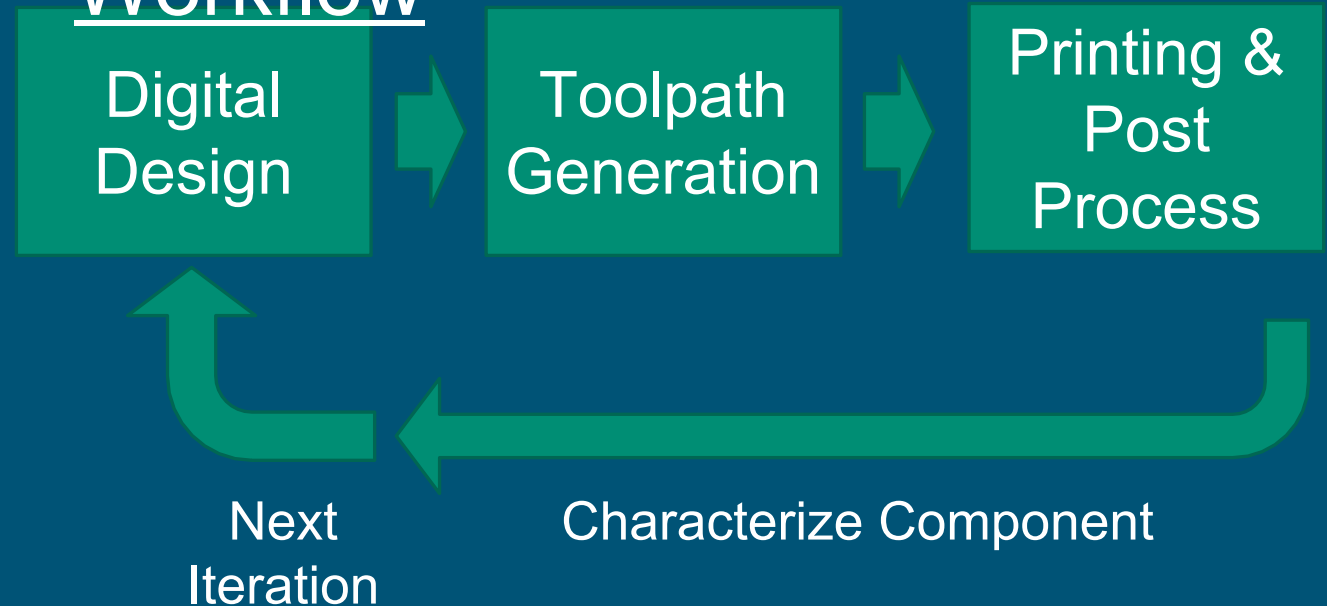
- Low-volume production.
- Rapid prototyping.

- **Techniques available for AM:**

- Syringe printing (200-500 μm resolution).
- Inkjet printing (50-100 μm resolution).
- Aerosol jet printing (10-50 μm resolution).

- While Aerosol Jet Printing can produce high resolution parts, the conductivity of the printed parts needs to be improved in order to minimize losses.

Additive Manufacturing Workflow

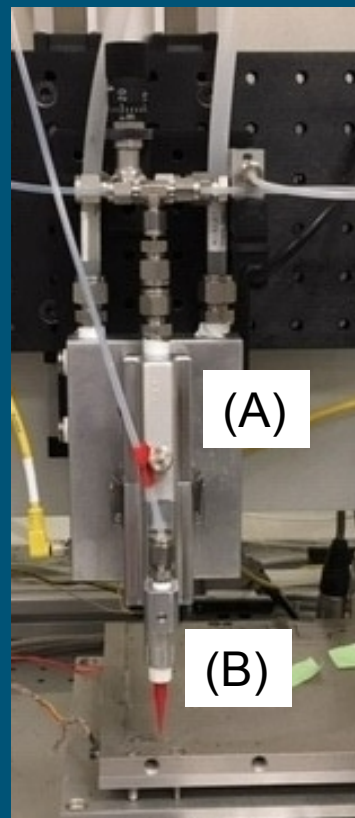


Aerosol Jet Printing (AJP) – IDS “Nanojet” Printer

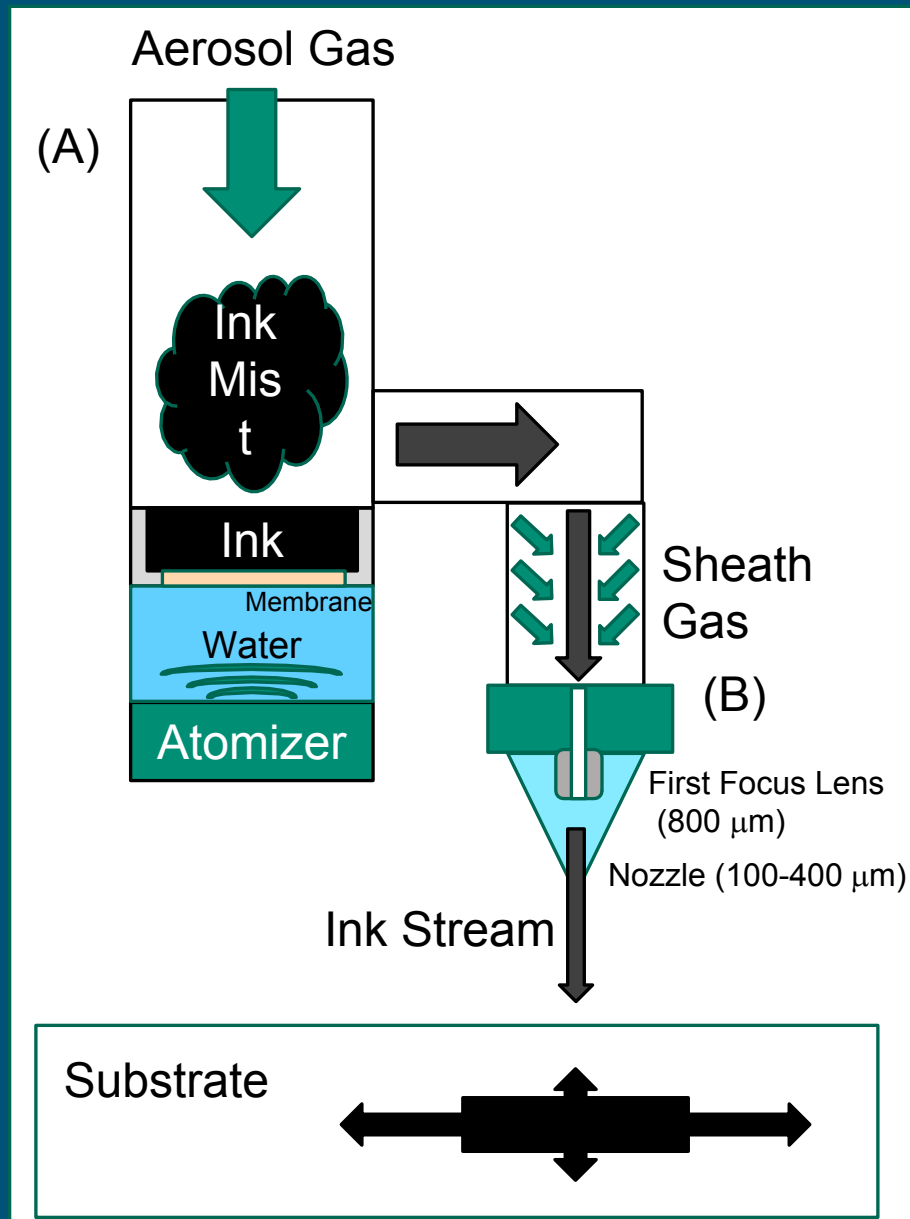


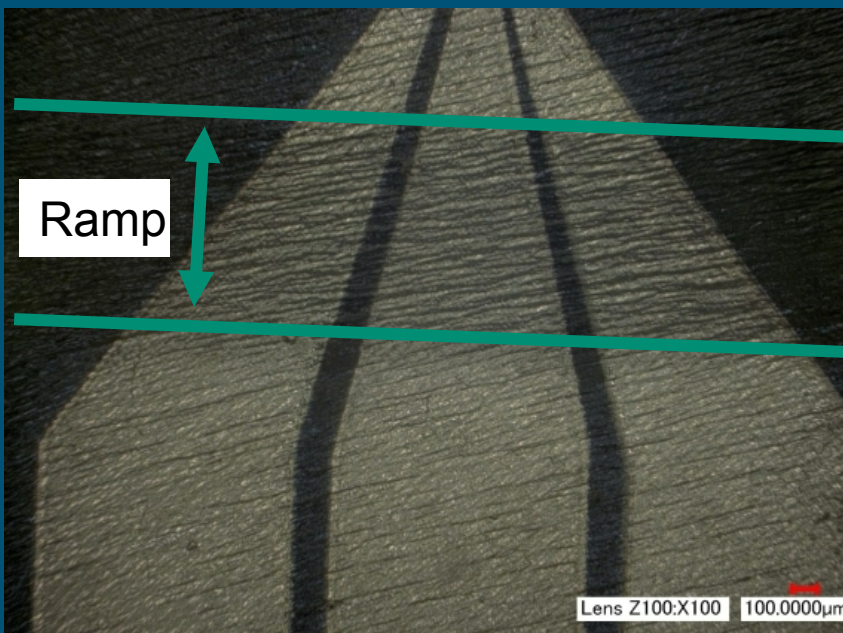
Principle of Operation:

- Low viscosity (<50 cps) ink is atomized by ultrasonic atomizer into an **ink mist**.
- Mist is driven to the nozzle by **aerosol gas**.
- **Sheath Gas** and **Aerodynamic Focusing Lenses** are used to focus the ink stream.
- Ink is dispensed through the nozzle onto a heated substrate where it solidifies.
- **Why AJP?**
 - High Precision: Can print lines as small as 10-50 μm .
 - Versatility: Supports a wide range of materials– metals, insulators, magnetic materials.
 - Flexible Stand Off Distance: Can support printing on curved and stepped surfaces with stand-off distance of 1-5 mm.

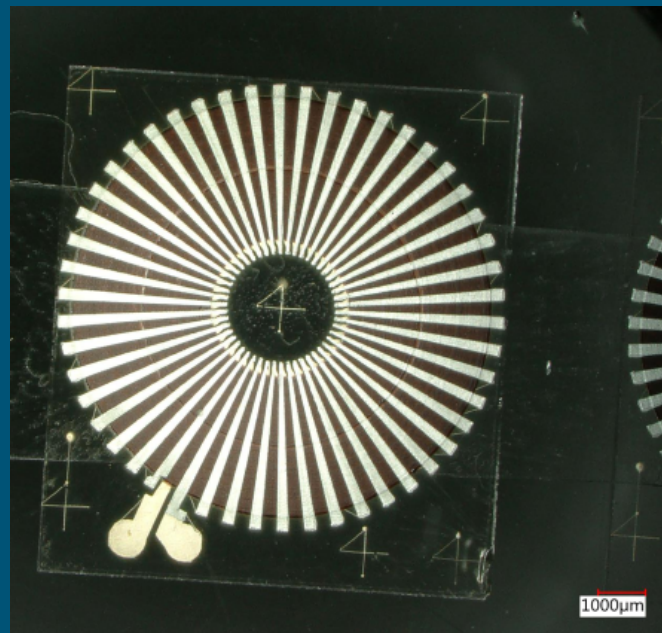


Nanojet Print Head

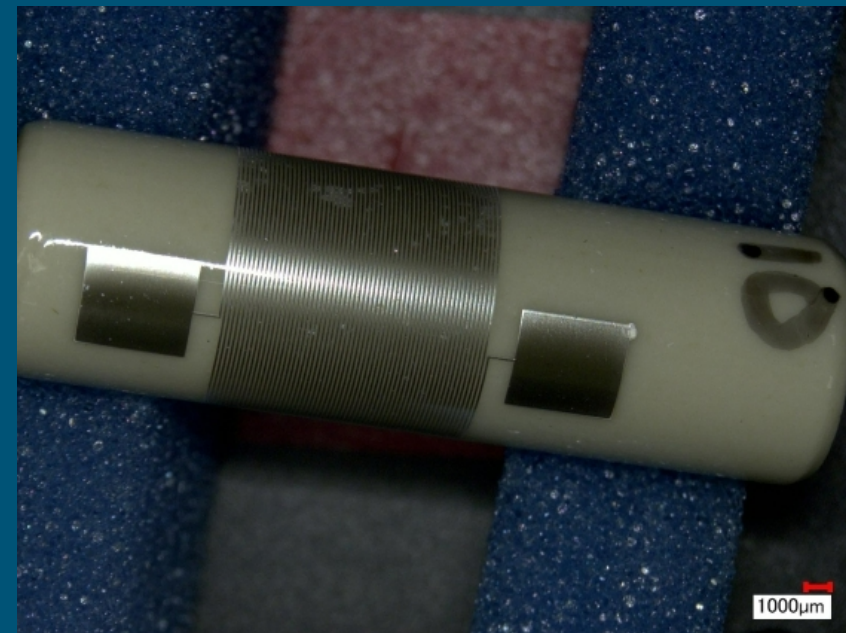




Non-Contact Printing:
Printing of interconnects
across a 500 μm tall ramp.



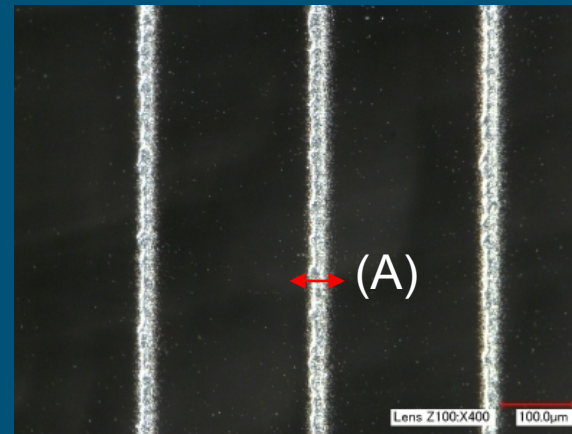
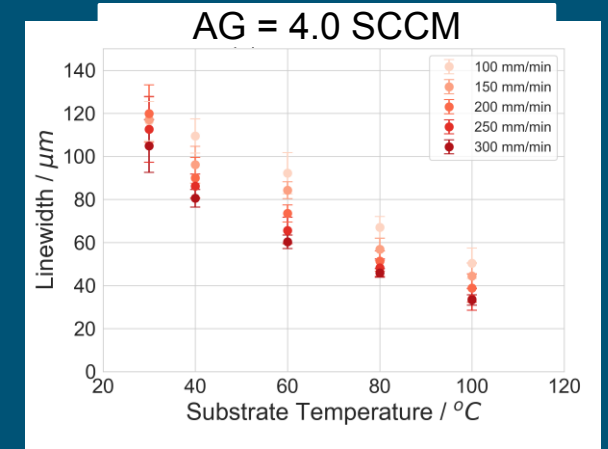
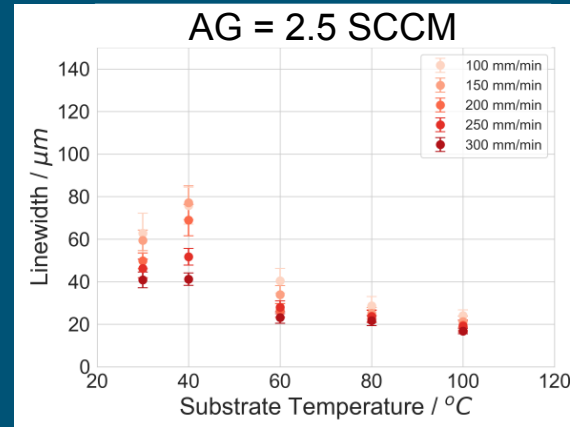
**Multi-material
Printing:** 3-layer
toroidal inductor with
magnetite core and
Ag windings.



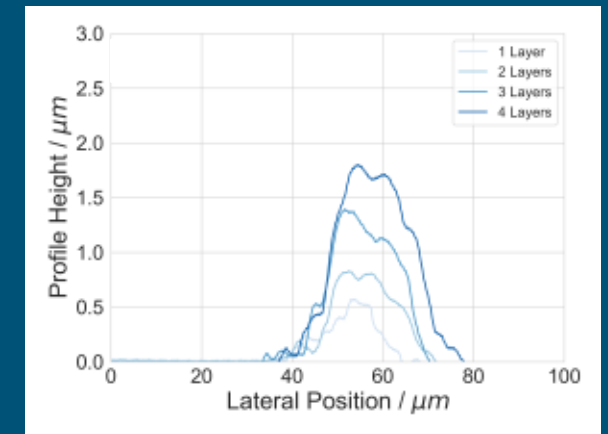
Rotational Printing:
Conformal printing
on cylindrical and
spherical surfaces.

High Resolution Printing

- Linewidth was measured on samples printed at:
 - AG = 2.0 – 4.0 SCCM
 - SG = 40 SCCM
 - Platen Temperature = 30 – 100°C
- Temperature of the substrate was identified to strongly influence linewidth.
- As temperature increases, the xylenes in the ink volatilize faster and the ink line is prevented from spreading on the surface.
- Linewidths of $< 20 \mu\text{m}$ are achievable with overspray inhibited.
- Line height increases from 0.5 to $1.75 \mu\text{m}$ with increasing number of layers from 1 to 4.



AG = 3.0 SCCM
SG = 40 SCCM
Substrate 100°C



Profilometry of (A)

Options to Improve Conductivity



Challenge: Although we can achieve fine resolution printing, nanoparticle Ag inks used in AJP only achieve ~15-25% bulk conductivity.

	Mechanism	Limitations
Multiple Layers	Increasing the number of layers increases the cross sectional area of the printed trace, decreasing resistance.	Increasing the number of layers decreases the line resolution due to ink spreading. Increases print time. Impractical for thick films (~10 μm).
Nanoparticle-free Reactive Inks	Chemical reaction produces large crystallites which have been demonstrated to achieve >73% of bulk Ag conductivity.[1]	High viscosity of reactive inks incompatible with ultrasonic atomization without dilution. Possible materials incompatibilities with ink housing. High processing temperature reported in [1] (300°C) limits available working substrates.



Electrodeposition and Electroless Deposition adds thicker, high density, high conductivity films without sacrificing resolution. AJP printed parts can be used as a templating layer.

Objectives and Procedure

- **Project Objective:** Develop methods to print planar spiral transformers for conversion of low voltage signals to high voltage signals.

- Transformers consist of a **Primary** and a **Secondary Inductor**.

- *Transformer Equation* [1]: $\frac{V_S}{V_P} = \frac{N_S}{N_P}$

Volts Turns

- Component Objectives:

- Primary inductor: 6 turn spiral. **Minimize resistance** ($\leq 1 \Omega$).
- Secondary inductor: **Maximizing the number of turns**.
Line widths 50-100 μm with gaps 50-100 μm .

- Deposition Conditions:

- Ink:
 - UTDots Ag40X Ag Nanoparticle Ink 20 v%.
 - Terpineol 20 v%.
 - Xylenes 60 v%.
- Sheath Gas: Xylenes saturated.
- Platen Temperature: 100°C.
- Number of Layers: 4.
- Post-Treatment: Anneal at 200°C for 3 hours.
- Substrate: Kapton.

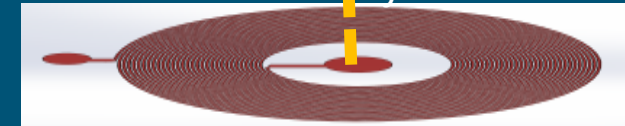
Transformer Components



Stacked Secondary Inductors



Dielectric
Layer



Dielectric Layer



Primary
Inductor

Kapton Substrate

Electrodeposition and Electroless Deposition

• Electrodeposition:

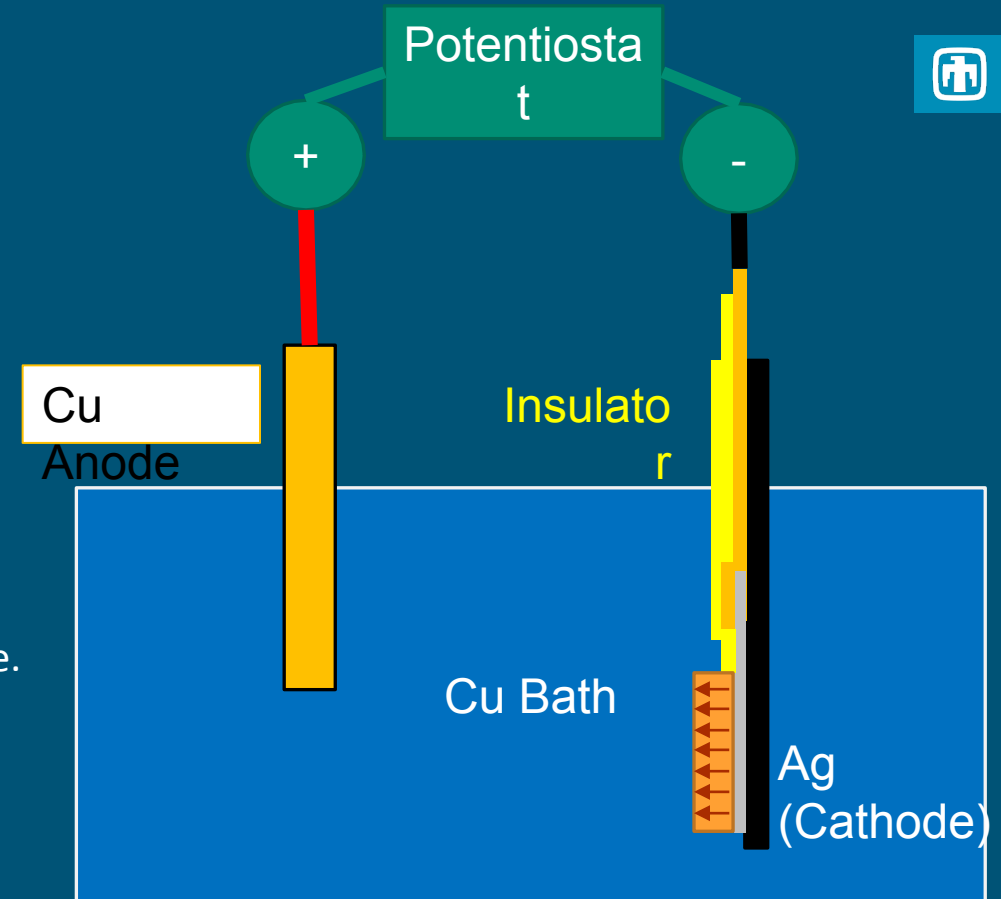
- Anode: $\text{Cu}_{(s)} \rightarrow 2\text{Cu}^{2+}_{(aq)} + 2e^-$
- Cathode: $\text{Cu}^{2+}_{(aq)} + 2e^- \rightarrow \text{Cu}_{(s)}$
- Electrolyte: Microfab SC + Microfab SC MD/LO
 - Cu^{2+} -17g/L
- **Pro:** Produces dense films with growth directed mainly by electric field.
- **Con:** Deposition rate is non-uniform if there is a large Ohmic drop across a sample.

• Electroless Deposition:

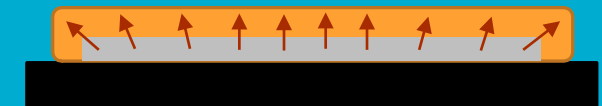
- Reaction [1]: $\text{Cu}^{2+} + 2\text{HCHO} + 4\text{OH}^- \rightarrow \text{Cu}(s) + 2\text{HCOO}^- + 2\text{H}_2\text{O} + \text{H}_2$
- Solution: Circuposit 3350-1 Electroless Cu Solution.
- **Pro:** Deposition occurs wherever Ag metal is present to catalyze reaction.
- **Con:** Less dense films which grow in all directions without electric field guidance.

• Combination Approach:

- Brief electroless deposition of printed Ag samples to reduce Ohmic resistance.
- Electrodeposition to further reduce resistance by depositing dense Cu.



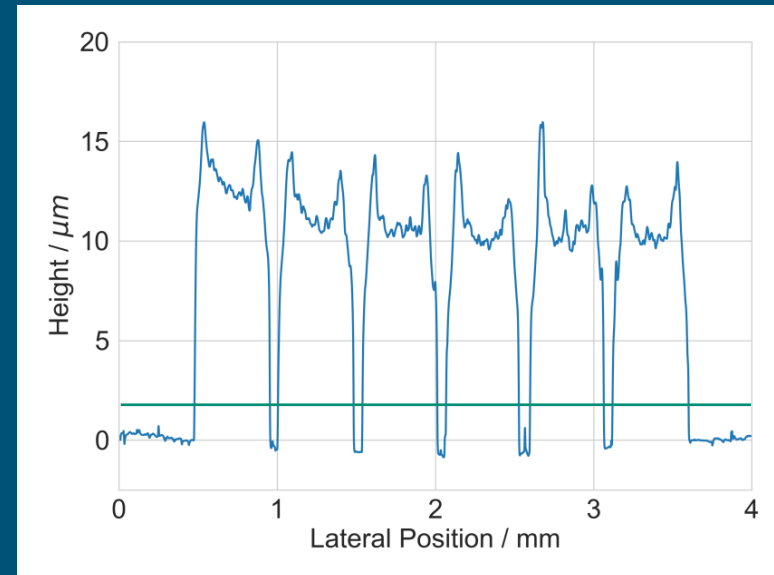
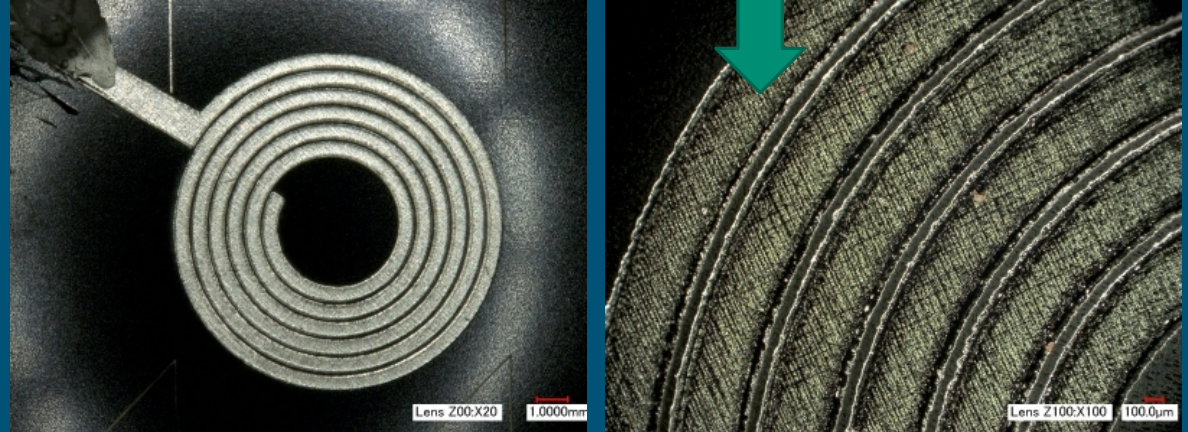
Electroless Plating Bath [1]





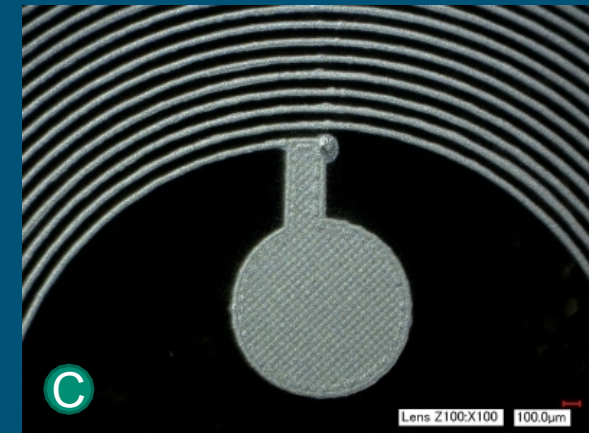
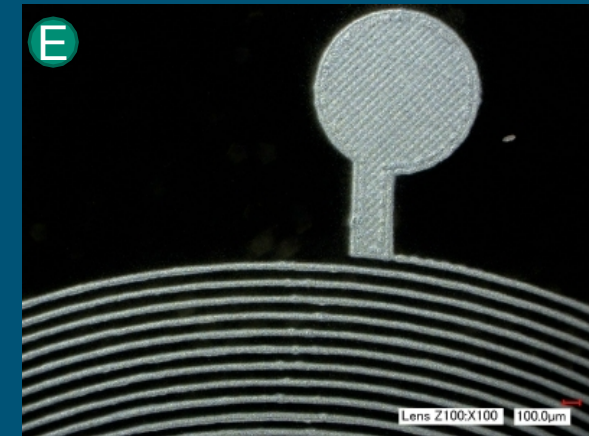
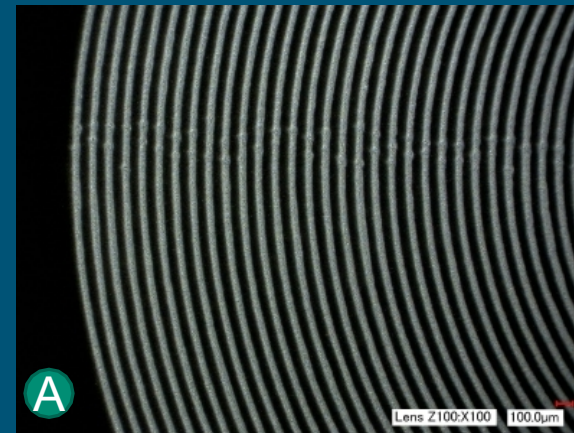
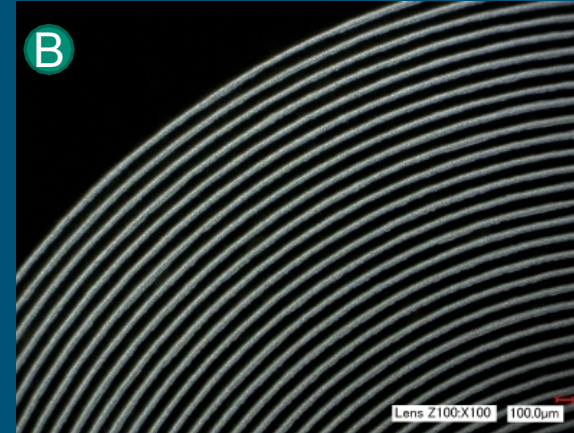
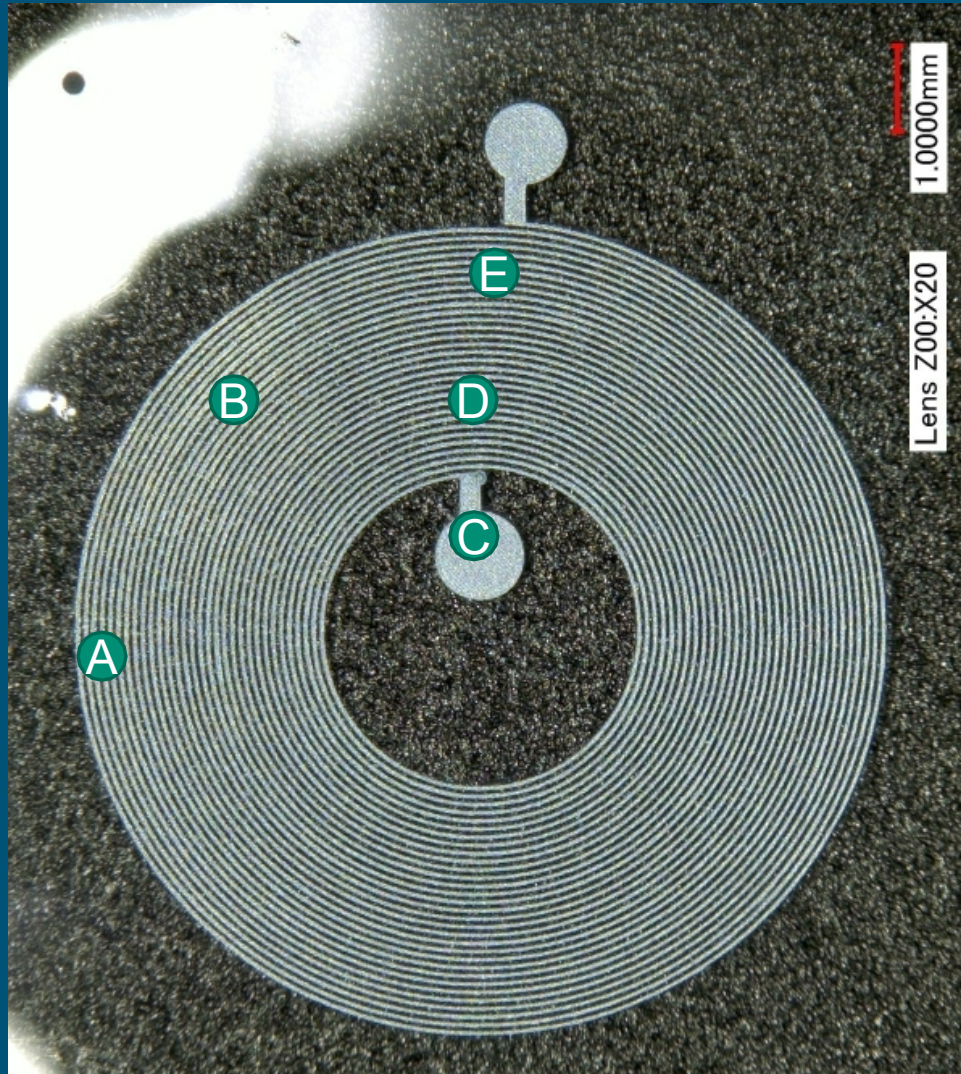
- Deposition Conditions:
 - 25 μm infill.
 - 4 layers.
 - 300 mm/min print speed.
- Modification by Electrodeposition:
 - Electrodeposition of Cu:
 - 30 mA/cm^2 – 30 min (Constant Current)
 - Follow up Ni plating in Ni Sulfamate plating bath for oxidation protection.
 - 15 mA/cm^2 – 1 min (constant Current)
- Electrodeposition increases thickness from $< 2 \mu\text{m}$ to $> 10 \mu\text{m}$.
- Traces remain well separated.
- Resistance decreases from 5Ω to $0.2\text{-}0.6 \Omega$, meeting objectives for resistance of the primary spiral design.
- No change in resistance after annealing at 200°C in air for 3 hours which enables building of multiple layers with air sintering steps.

450 μm linewidth



Starting
Thickness
~ 1 micron

Secondary Inductor – As Printed



- Deposited with 25 μm infill with pads, single curve for spirals, 300 mm/min speed.
- Lines are well separated (33 μm linewidth + 60 μm gap) with no visible

Secondary Inductor – Electroless Deposition



- The long length of the secondary inductor introduces high Ohmic resistance which suppresses uniform deposition.
- Samples were immersed in an electroless deposition plating bath at 42°C from 5-20 minutes with no agitation.
- Samples immersed for 15-20 minutes showed delamination of Cu. High stresses during growth of Cu



2.5 min

Incomplete Coverage

5 min

Continuous coverage of Cu

10 min

15 min

Delamination due to stresses built up during deposition

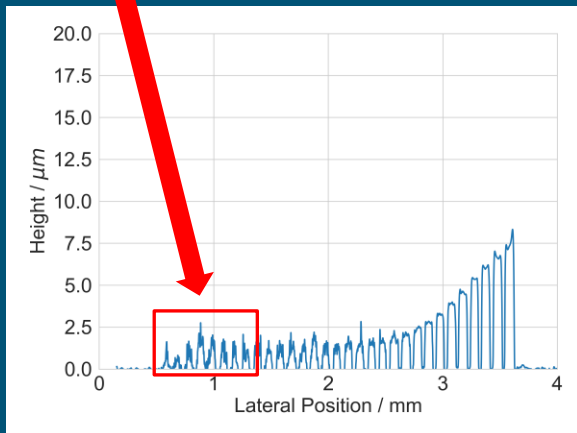
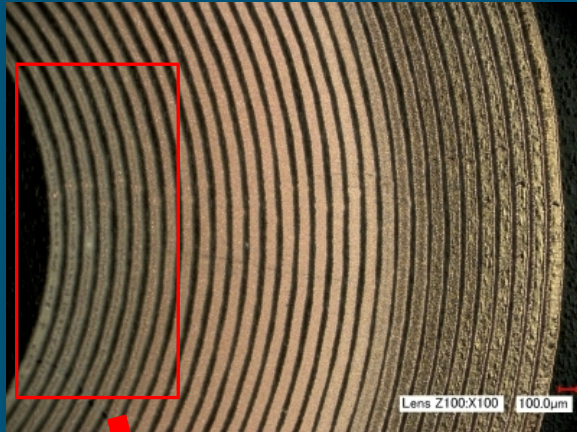
20 min

Follow up these samples with electrodeposition.

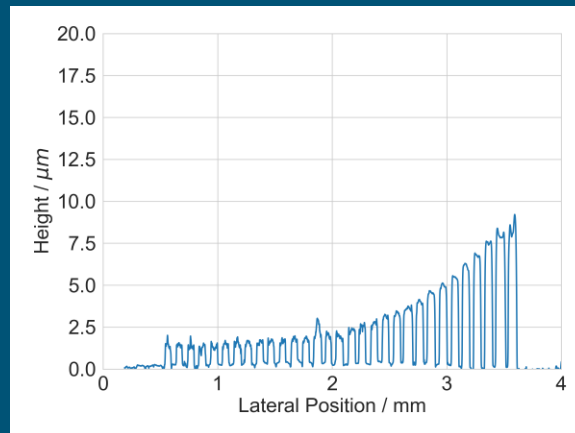
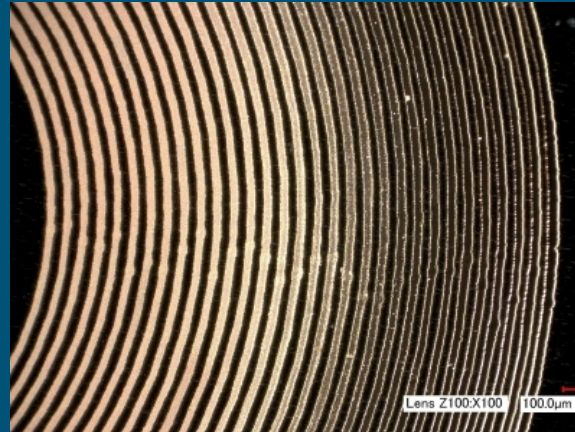
Secondary Inductor - Electrodeposition



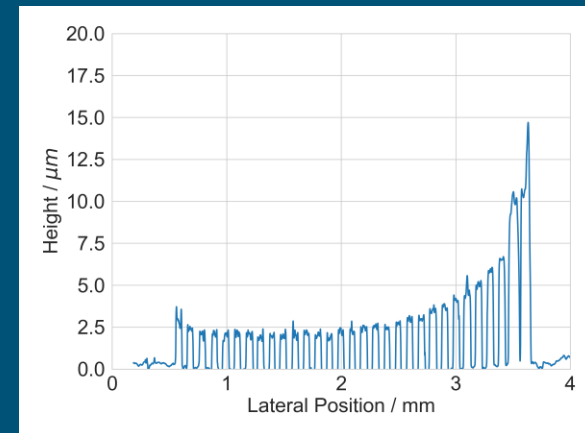
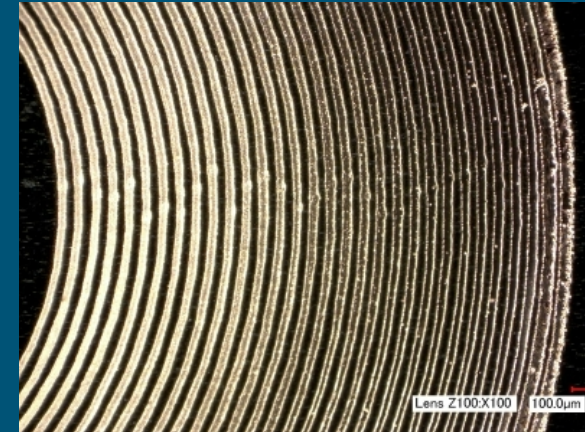
AJP Ag only



Ag + Electroless 5 min



Ag + Electroless 10 min



- All samples deposited at 11 mA/cm^2 for 15 minutes in a constant current configuration.
- Deposition of Cu is inhibited due to high Ohmic resistance towards the interior of the spirals.
- Increased deposition at the spiral interior is observed with electroless deposition modification prior to electrodeposition

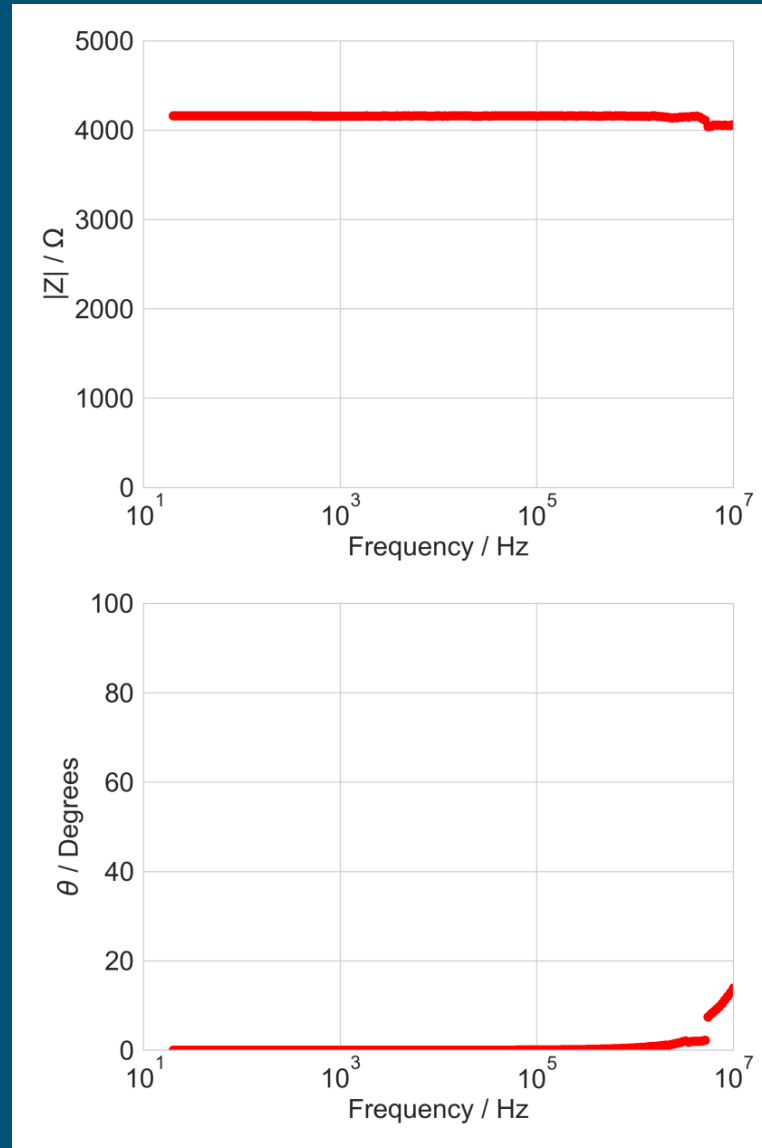
Impedance Analysis

- Impedance measurements on the secondary were taken on a Keysight E4990A from 20 Hz up to 10 MHz with an oscillation voltage of 500 mV.
- Impedance spectra were fit to a circuit model:
 - $R - L$ (Resistor in series with Inductor)

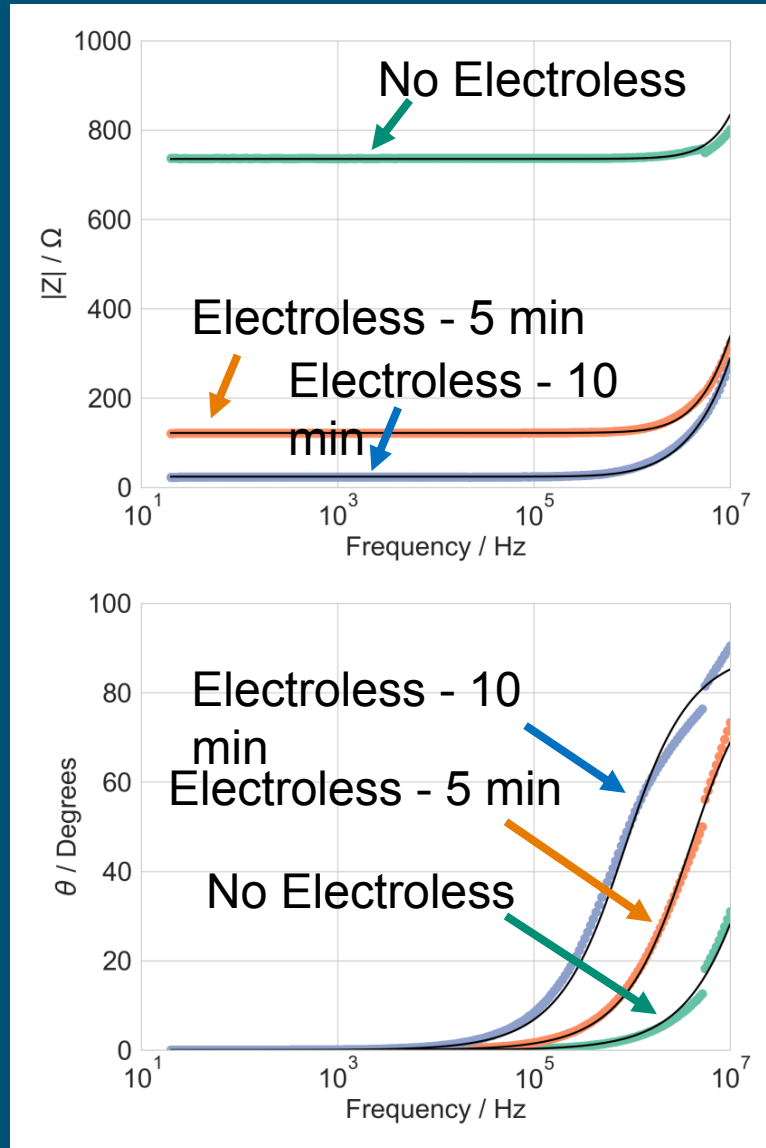
Ag only	Ag only	5 min Electroless	10 min Electroless
Without Cu	Cu Electrodeposition		
$R = 4.15 \text{ k}\Omega$	$R = 736 \Omega$	$R = 121 \Omega$	$R = 20.0 \Omega$
$L = \text{N/A}$	$L = 5.5 \mu\text{H}$	$L = 5.0 \mu\text{H}$	$L = 4.6 \mu\text{H}$
Resistance Improvement	X 5.6	X 34	X 208

- Without electrodeposition, response completely dominated by $4.15 \text{ k}\Omega$ Ohmic resistance. Inductance could be measured after electrodeposition to be $4.6\text{-}5.5 \mu\text{H}$.
- Up to **208x decrease** in resistance observed after electrodeposition.

Ag Only



Ag + Cu Electrodeposition



— Circuit Model Fit

Conclusions

We have demonstrated the capability to deposit electronic components of high resolution and low resistance with a combined aerosol jet printing and electroless and/or electrodeposition approach.

The resistance for primary inductors was reduced to below 1 Ω and resistance of secondary inductors was reduced by 208X.

Electrodeposition was successfully able to recover the inductive behavior from the printed secondary and inductances around 4.6-5.5 μH were measured.

Future Work:

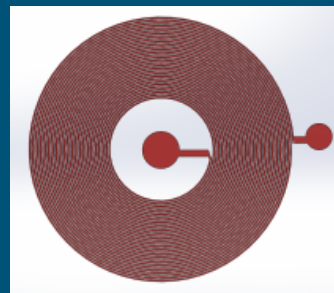
- Apply printing of dielectric polymers to separate layers and integrate the inductors into a working transformer device.

Acknowledgements:

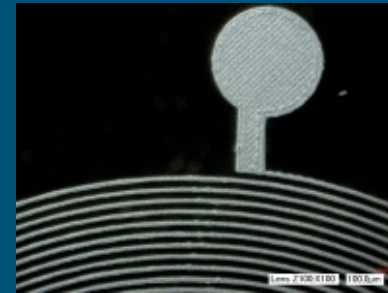
We thank Jamin Pillars and Christian Arrington (Sandia National Labs) for their assistance with developing the electrodeposition/electroless processes. We also acknowledge Sam Strong (Sandia National Labs) for assistance with optimization of printing hardware, and Emily Weigel (Sandia National Labs) for assistance with electroless deposition and profilometry.

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CAD



Aerosol Jet



Electroless
Deposition



Electrodeposition

